

**METHOD FOR REPAIRING OPAQUE DEFECTS ON SEMICONDUCTOR
MASK RETICLES**

ABSTRACT

[0027] A method is disclosed for repairing an opaque defect on a mask substrate. After examining one or more opaque patterns in a predetermined area of the mask substrate, at least one opaque defect in the opaque patterns is identified based on a difference between its light reflection rate and a reference reflection rate. A residue height of the opaque defect is further determined based on its light transmission rate, and a repair formula such as an etching dosage is devised based on the determined residue height.